

PREPARATION OF A CHK1 INHIBITOR COMPOUND

This invention relates to processes for preparing the Chk-1 inhibitor compound 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile, processes for preparing synthetic intermediates, and to novel chemical intermediates for use in the processes.

Background of the Invention

- Chk-1 is a serine/threonine kinase involved in the induction of cell cycle checkpoints in response to DNA damage and replicative stress [Tse et al, *Clin. Can. Res.* 2007;13(7)]. Cell cycle checkpoints are regulatory pathways that control the order and timing of cell cycle transitions. Many cancer cells have impaired G1 checkpoint activation. For example, Hahn *et al.*, and Hollstein *et al.*, have reported that tumours are associated with mutations in the p53 gene, a tumour suppressor gene found in about 50% of all human cancers [N Engl J Med 2002, 347(20):1593; Science, 1991, 253(5015):49].
- Chk-1 inhibition abrogates the intra S and G2/M checkpoints and has been shown to selectively sensitise tumour cells to well known DNA damaging agents. Examples of DNA damaging agents where this sensitising effect has been demonstrated include Gemcitabine, Pemetrexed, Cytarabine, Irinotecan, Camptothecin, Cisplatin, Carboplatin [*Clin. Cancer Res.* 2010, 16, 376], Temozolomide [*Journal of Neurosurgery* 2004, 100, 1060], Doxorubicin [*Bioorg. Med. Chem. Lett.* 2006;16:421-6], Paclitaxel [WO2010149394], Hydroxy urea [*Nat. Cell. Biol.* 2005;7(2):195-20], the nitroimidazole hypoxia-targeted drug TH-302 (Meng *et al.*, AACR, 2013 Abstract No. 2389) and ionising radiation [*Clin. Cancer Res.* 2010, 16, 2076]. See also the review article by McNeely et al., [*Pharmacology & Therapeutics* (2014), 142(1):1-10]
- Recently published data have also shown that Chk-1 inhibitors may act synergistically with PARP inhibitors [*Cancer Res* 2006.; 66:(16)], Mek inhibitors [*Blood.* 2008; 112(6): 2439–2449], Farnesyltransferase inhibitors [*Blood.* 2005;105(4):1706-16], Rapamycin [*Mol. Cancer Ther.* 2005;4(3):457-70], Src inhibitors [*Blood.* 2011;117(6):1947-57] and WEE1 inhibitors [Carrassa, 2021, 11(13):2507; Chaudhuri *et al.*, *Haematologica*, 2014 99(4):688.].

Furthermore, Chk-1 inhibitors have demonstrated an advantage when combined with immunotherapy agents [Mouw et al., Br J Cancer, 2018. (7):933]. Chk1 inhibitors have been shown to activate cGAS, which induces an innate immune response through STING signaling, and to induce PD-L1 expression and synergize with anti-PD-L1 in

vivo [Sen et al., *Cancer Discov* 2019 (5):646; Sen et al., *J Thorac Oncol*, 2019, (12):2152].

Resistance to chemotherapy and radiotherapy, a clinical problem for conventional therapy, has been associated with activation of the DNA damage response in which
5 Chk-1 has been implicated [*Nature*; 2006; 444(7):756-760; *Biochem. Biophys. Res. Commun.* 2011 ;406(1):53-8].

It is also envisaged that Chk-1 inhibitors, either as single agents or in combination, may be useful in treating tumour cells in which constitutive activation of DNA damage and checkpoint pathways drive genomic instability in particular through replication
10 stress. This phenotype is associated with complex karyotypes, for example in samples from patients with acute myeloid leukemia (AML) [*Cancer Research* 2009, **89**, 8652]. *In vitro* antagonisation of the Chk-1 kinase with a small molecule inhibitor or by RNA interference strongly reduces the clonogenic properties of high-DNA damage level AML samples. In contrast Chk-1 inhibition has no effect on normal hematopoietic
15 progenitors. Furthermore, recent studies have shown that the tumour microenvironment drives genetic instability [*Nature*; 2008;(8):180-192] and loss of Chk-1 sensitises cells to hypoxia/reoxygenation [*Cell Cycle*; 2010; 9(13):2502]. In neuroblastoma, a kinome RNA interference screen demonstrated that loss of Chk-1 inhibited the growth of eight neuroblastoma cell lines. Tumour cells deficient in
20 Fanconi anemia DNA repair have shown sensitivity to Chk-1 inhibition [*Molecular Cancer* 2009, **8**:24]. It has been shown that the Chk-1 specific inhibitor PF-00477736 inhibits the growth of thirty ovarian cancer cell lines [Bukczynska et al, 23rd Lorne Cancer Conference] and triple negative breast cancer cells [*Cancer Science* 2011, **102**, 882]. Also, PF-00477736 has displayed selective single agent activity in a MYC
25 oncogene driven murine spontaneous cancer model [Ferrao et al, *Oncogene* (15 August 2011)]. Chk-1 inhibition, by either RNA interference or selective small molecule inhibitors, results in apoptosis of MYC-overexpressing cells both *in vitro* and in an *in vivo* mouse model of B-cell lymphoma [Höglund et al., *Clinical Cancer Research*, 2011]. The latter data suggest that Chk-1 inhibitors would have utility for
30 the treatment of MYC-driven malignancies such as B-cell lymphoma/leukemia, neuroblastoma and some breast and lung cancers. Chk-1 inhibitors have also been shown to be effective in pediatric tumour models, including Ewing's sarcoma and rhabdomyosarcoma [Lowery, 2018. *Clin Cancer Res* 2019, 25(7):2278]. Chk1 inhibitors have been shown to be synthetically lethal with the B-family of DNA
35 polymerases, resulting in increased replication stress, DNA damage and cell death [Rogers et al., 2020, 80(8);1735]. Other cell cycle regulated genes have also been

reported to confer sensitivity to Chk-1 inhibitors, including CDK2 and POXM1 [Ditano et al., 20201. 11(1);7077; Branigan et al., 2021 Cell Reports 34(9):1098808]

It has also been reported that mutations that reduce the activity of DNA repair pathways can result in synthetically lethal interactions with Chk1 inhibition. For example, mutations that disrupt the RAD50 complex and ATM signaling increase responsiveness to Chk1 inhibition [Al-Ahmadie et al., Cancer Discov. 2014. (9):1014-21]. Likewise, deficiencies in the Fanconi anemia homologous DNA repair pathway lead to sensitivity to Chk1 inhibition [Chen et al., Mol. Cancer 2009 8:24, Duan et al., Frontiers in Oncology 2014 4:368]. Also, human cells that have loss of function in the Rad17 gene product are sensitive to Chk1 suppression [Shen et al., Oncotarget, 2015. 6(34):35755].

Various attempts have been made to develop inhibitors of Chk-1 kinase. For example, WO 03/10444 and WO 2005/072733 (both in the name of Millennium) disclose aryl/heteroaryl urea compounds as Chk-1 kinase inhibitors. US2005/215556 (Abbott) discloses macrocyclic ureas as kinase inhibitors. WO 02/070494, WO2006014359 and WO2006021002 (all in the name of Icos) disclose aryl and heteroaryl ureas as Chk-1 inhibitors. WO/2011/141716 and WO/2013/072502 both disclose substituted pyrazinyl-phenyl ureas as Chk-1 kinase inhibitors. WO2005/009435 (Pfizer) and WO2010/077758 (Eli Lilly) disclose aminopyrazoles as Chk-1 kinase inhibitors. WO2015/120390 discloses a class of substituted phenyl-pyrazolyl-amines as Chk-1 kinase inhibitors. One of the compounds disclosed is the compound 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile, the synthesis of which is described in Example 64 and Synthetic Method L in WO2015/120390.

The Chk-1 kinase inhibitor compound 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile is useful in the treatment of cancers as disclosed in WO2015/120390.

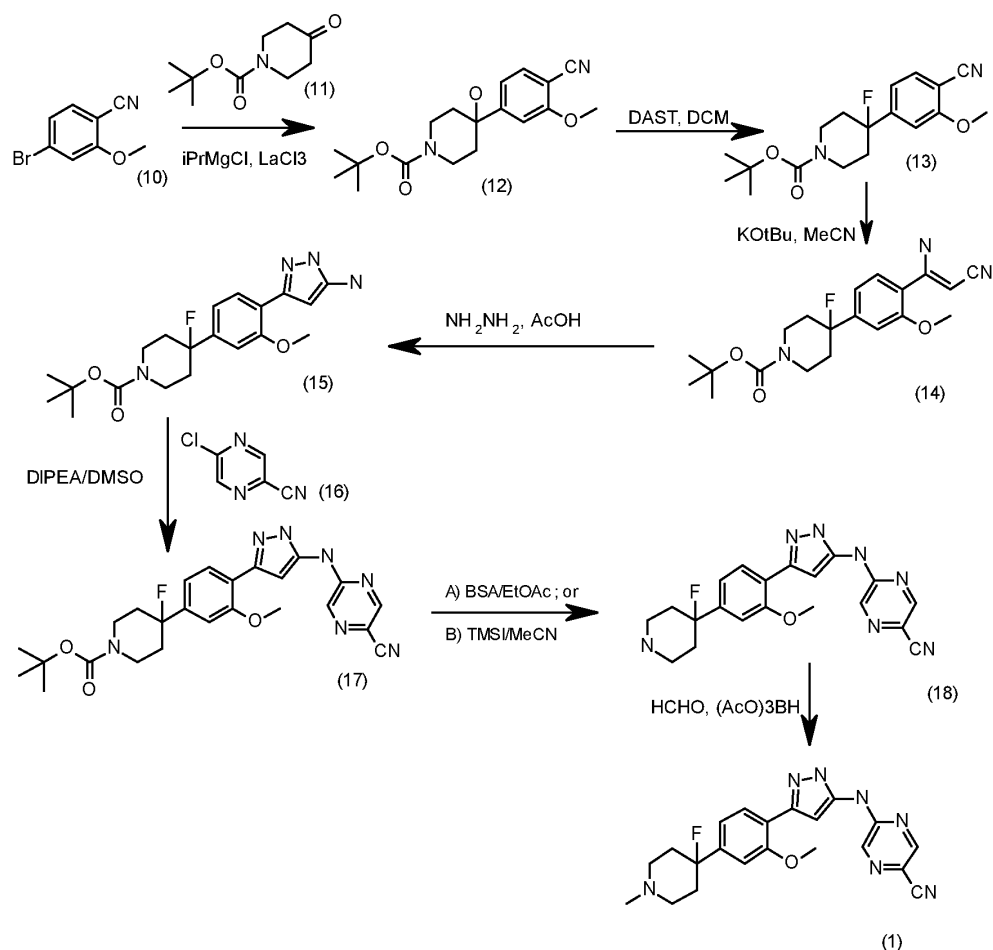
WO2018/183891 (Cascadian Therapeutics) discloses combinations of the compound 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile or a pharmaceutically acceptable salt thereof with WEE-1 inhibitors.

The Invention

The present invention provides improved processes for making the Chk-1 kinase inhibitor compound 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-

pyrazol-3-yl]amino]pyrazine-2-carbonitrile (referred to herein also as the compound of formula (I) or the Chk-1 inhibitor).

In one general aspect, the improved process of the present invention is represented by the sequence of reactions set out in Scheme 1 below.



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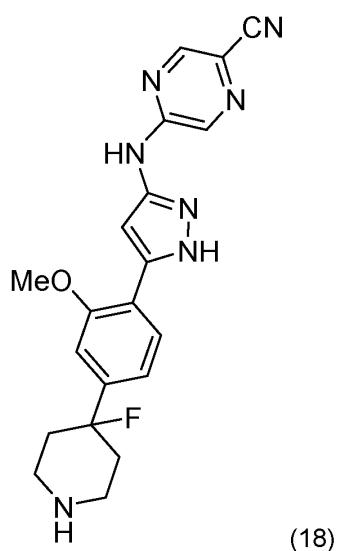
Scheme 1

The synthetic route shown in Scheme 1 has a number of advantages over the synthetic route described in WO2015/120390. For example, the route depicted in Scheme 1 is shorter in terms of the total steps (7 vs 9). Many of the intermediates derived from the process are readily isolable crystalline solids. The new route therefore also makes use of these crystalline intermediates to remove the need for chromatography and thereby is a more scalable process. In addition, the improved process avoids the use of certain reagents in WO2015/120390 which are undesirable for large scale synthesis (e.g. Dess-Martin periodinane and $n\text{-BuLi}$).

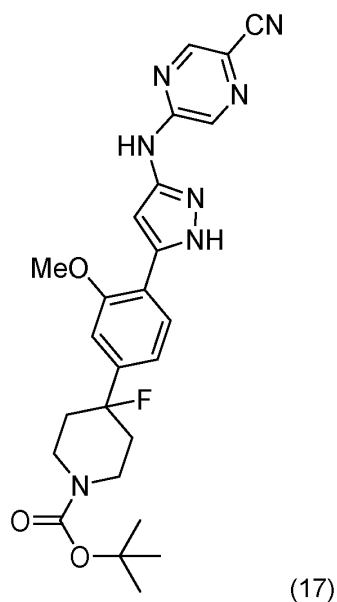
The improved synthetic route makes use of the same final step (reductive methylation) as the synthetic route described in WO 2015/120390 but the deprotection and synthesis of the Boc-protected intermediate of formula (17) in the present route differ from the synthesis and deprotection of intermediate of formula (17) in

5 WO2015/120390.

Accordingly, in one aspect (Embodiment 1.1), the invention provides a process for the preparation of a compound of the formula (18):



which process comprises reacting a compound of the formula (17):



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with an alkylsilyl halide or a sulphonic acid (such as benzenesulphonic acid).

The deprotection of Boc-protected intermediate of formula (17) in WO 2015/120390 made use of hydrochloric acid. However, it was found that residual amounts of hydrochloric acid present in the deprotected intermediate of formula (18) reacted with formaldehyde used in the subsequent reductive methylation in the reaction to form potential genotoxic impurities, for example the known carcinogen bis(chloromethyl) ether, (BCME). The improved process utilises either an alkylsilyl halide or benzenesulphonic acid (BSA) and has been found to avoid the generation of potential genotoxic impurities and other impurities in the final product. The process may further comprise reducing the water content of the starting material in order to give a cleaner deprotection step. However, the use of an alkylsilyl halide has been found to tolerate the presence of water in the starting material and therefore an advantage of using an alkyl alkylsilyl halide over BSA is that it avoids the need for a pre-reaction drying step. The use of alkylsilyl halide also reduces the reaction temperature and reaction time and avoids the use of reagents that may contain benzene impurities.

In further embodiments, the invention provides:

- 1.2 A process according to Embodiment 1.1 comprising reacting a compound of the formula (17) with an alkylsilyl halide.
- 1.3 A process according to Embodiment 1.2 wherein the alkylsilyl halide is a trimethyl silyl halide.
- 1.4 A process according to Embodiment 1.3 wherein the alkylsilyl halide is trimethylsilyl iodide (TMSI).
- 1.5 A process according to any one of Embodiments 1.1 to 1.4 wherein the reaction is carried out in the presence of a polar, aprotic solvent.
- 1.6 A process according to Embodiment 1.5 wherein the polar, aprotic solvent is acetonitrile.
- 1.7 A process according to any one of Embodiments 1.1 to 1.6 wherein the reaction is carried out at a temperature of from 0 °C to 20 °C.
- 1.8 A process according to any one of Embodiments 1.1 to 1.7 wherein the reaction is carried out for a period of from 15 minutes to 60 minutes, for example for a

period of approximately 30 minutes and is optionally followed by the addition of a base (such as an alkali metal carbonate, e.g. potassium carbonate).

1.9 A process according to Embodiment 1.1 comprising reacting a compound of the formula (17) with a sulphonic acid, such as benzenesulphonic acid.

5 1.10 A process according to Embodiment 1.9 wherein the reaction is carried out in the presence of a polar, aprotic solvent.

1.11 A process according to Embodiment 1.10 wherein the polar, aprotic solvent is ethyl acetate.

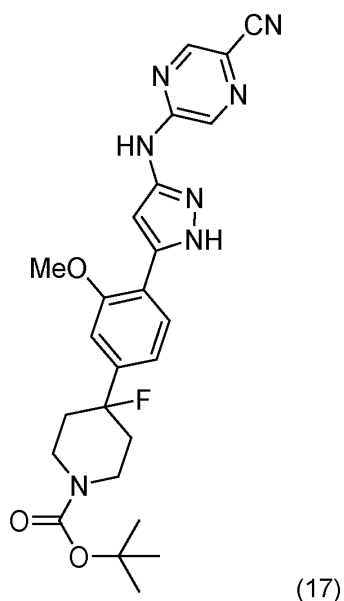
10 1.12 A process according to any one of Embodiments 1.9 to 1.11 wherein the reaction is carried out at a temperature of from 50 °C to 70 °C, for example at a temperature of approximately 60 °C.

1.13 A process according to any one of Embodiments 1.9 to 1.11 wherein the reaction is carried out for a period of from 20 hours to 30 hours, for example for a period of approximately 26 hours.

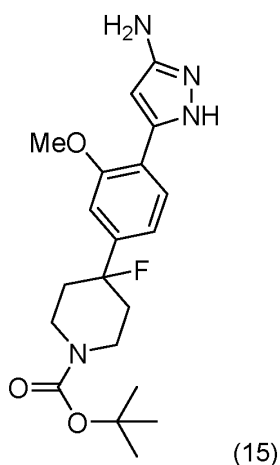
15 1.14 A process according to any one of Embodiments 1.9 to 1.11 which, prior to reacting the compound of formula (17) with benzenesulphonic acid, comprises the step of reducing the water content of the starting material.

20 1.15 A process according to Embodiment 1.14 wherein the step of reducing the water content of the starting material involves heating the compound of formula (17) in a non-polar solvent (such as 1,4-dioxane), for example at a temperature of from 80 °C to 85 °C, and then removing the non-polar solvent.

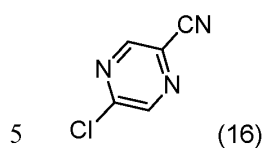
In another aspect (Embodiment 2.1) the invention provides a process for the preparation of a compound of the formula (17):



which process comprises the reaction of a compound of the formula (15)



with a compound of the formula (16):



In WO 2015/120390, Boc-protected intermediate of formula (17) was formed by the reaction of intermediate of formula (15) with 5-bromopyrazine-2-carbonitrile. By contrast, the improved process makes use of 5-chloropyrazine-2-carbonitrile. In addition, in the improved process, the reaction is conducted at a lower temperature than described in WO 2015/120390 (50°C rather than 80°C).

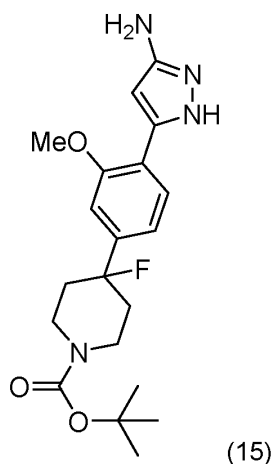
Furthermore, it has been found that conducting the reaction in anhydrous conditions reduces the formation of unwanted side-products/impurities.

In further embodiments, the invention provides:

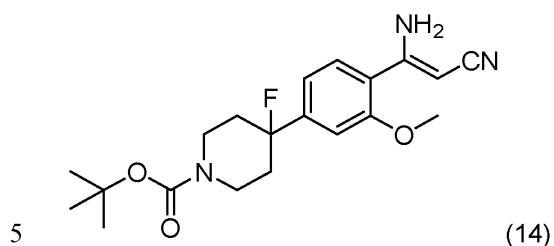
- 2.2 A process according to Embodiment 2.1 wherein the reaction is carried out in the reaction is carried out in a non-aqueous aprotic solvent.
- 2.3 A process according to Embodiment 2.2 wherein the solvent is dimethyl sulphoxide (DMSO).
- 2.4 A process according to any one of Embodiments 2.1 to 2.3 wherein the solvent is anhydrous, for example wherein the solvent has a water content of 500ppm or less.
- 2.5 A process according to any one of Embodiments 2.1 to 2.3 wherein the reaction is carried out in the presence of diisopropylethylamine (DIPEA).
- 2.6 A process according to any one of Embodiments 2.1 to 2.5 wherein the process is carried out at a temperature in the range from 40 °C to 80 °C, e.g. about 70 °C.
- In the improved process, the method of preparing intermediate of formula (15) is entirely different to the method used in WO 2015/120390. The improved method results in a number of advantages described below, including:
- The use of crystalline intermediates (which reduces the need for chromatographic purification of intermediates)
 - The lowest temperature used is -10 °C, making the process more suitable for scaling (the route described in WO 2015/120390 involved two reaction steps that were conducted at -78 °C)
 - The reactions being higher yielding
 - Avoiding the use of Dess-Martin periodinane as an oxidizing reagent. Use of this reagent on an industrial scale is made difficult by its cost and its potentially explosive nature (see Plumb, J.B.; Harper, D.J. (1990). "Chemical Safety: 2-Iodoxybenzoic acid". Chem. Eng. News. 68: 3. doi:10.1021/cen-v068n029.p002)

Further specific advantages are discussed in relation to each step below.

In a further aspect (Embodiment 3.1), the invention provides a process for the preparation of a compound of formula (15):



which process comprises reacting a compound of the formula (14):



with hydrazine (NH_2NH_2).

This process results in an improved yield compared to the corresponding process for the formation of a compound of formula (15) in WO 2015/120390 (see Example 64). The improved process results in a yield of 58% compared to a yield of 44% obtained with the process of Example 64.

In further embodiments, the invention provides:

3.2 A process according to Embodiment 3.1 wherein the reaction is carried out in a polar, protic solvent.

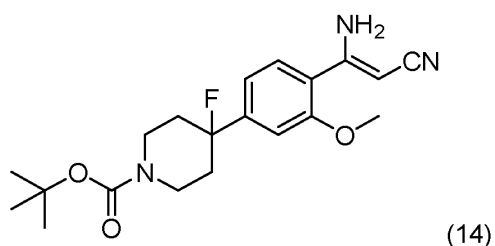
3.3 A process according to Embodiment 3.2 wherein the polar, protic solvent is a C_{1-4} alcohol, such as ethanol (EtOH).

3.4 A process according to any one of Embodiments 3.1 to 3.3 wherein the reaction is carried out in the present of glacial acetic acid.

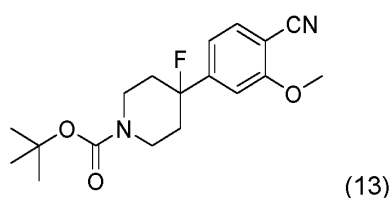
3.5 A process according to any one of Embodiment 3.1 to 3.4 wherein the reaction is carried out at a temperature of 70 °C to 80 °C, for example at a temperature of approximately 75 °C.

3.6 A process according to any one of Embodiments 3.1 to 3.5 wherein the reaction is carried out for a time period of 4 hours or less, for example from 1 hour to 3 hours, such as for approximately 2 hours.

In a further aspect (Embodiment 4.1), the invention provides a process for the preparation of a compound of the formula (14):



which process comprises reacting a compound of formula (13):



with acetonitrile (CH₃CN) in the presence of a base.

In further embodiments, the invention provides:

4.2 A process according to Embodiment 4.1 wherein the base is an alkoxide base.

4.3 A process according to Embodiment 4.2 wherein the base is a tert-butoxide base.

4.4 A process according to Embodiment 4.3 wherein the base is KO^tBu.

4.5 A process according to any one of Embodiments 4.1 to 4.4 wherein the reaction is carried out in a polar, aprotic solvent.

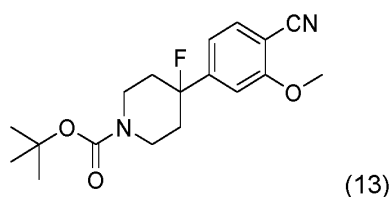
4.6 A process according to Embodiment 4.5 wherein the solvent is tetrahydrofuran (THF) or diethyl ether.

4.7 A process according to any one of Embodiment 4.1 to 4.6 wherein the reaction is carried out at a temperature of 30 °C to 50 °C, for example at a temperature of approximately 40 °C.

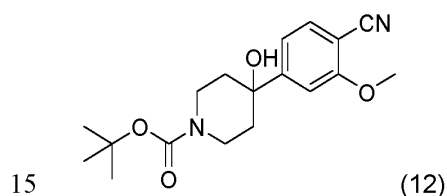
4.8 A process according to any one of Embodiments 4.1 to 4.7 wherein the reaction is carried out for a time period of from 3 hours to 5 hours, for example for a time period of approximately 4 hours.

The compound of formula (13) is prepared by the fluorination of the corresponding alcohol compound of formula (12).

Accordingly, in a further aspect (Embodiment 5.1), the invention provides a process for the preparation of a compound of the formula (13):



which process comprises reacting a compound of formula (12):



with a deoxyfluorination reagent.

In further embodiments, the invention provides:

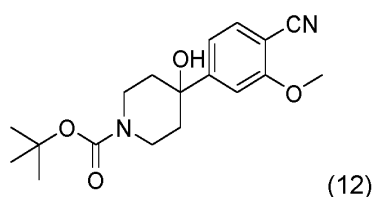
5.2 A process according to Embodiment 5.1 wherein the deoxyfluorination reagent is diethylaminosulphur trifluoride DAST.

5.3 A process according to Embodiment 5.1 or Embodiment 5.2 wherein the reaction is carried out in a polar, aprotic solvent.

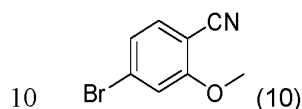
5.4 A process according to Embodiment 5.3 wherein the solvent is dichloromethane (DCM).

5.5 A process according to any one of Embodiments 5.1 to 5.4 wherein the reaction is carried out at a temperature of between -20 °C and -10°C (for example, at approximately -10°C).

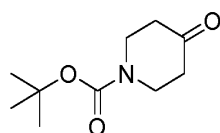
In a further aspect (Embodiment 6.1), the invention provides a process for the preparation of a compound of the formula (12):



which process comprises reacting a compound of formula (10):



with a compound of formula (11):



in the presence of a metallating agent, such as a Grignard reagent.

The reaction is typically carried out in the presence of a Grignard reagent and a Lewis acid, for example LaCl_3 . It has been found that the LaCl_3 reagent acts as a chelating reagent and reduces the formation of impurities.

Accordingly, in further embodiments, the invention provides:

6.2 A process according to Embodiment 6.1 wherein the reaction is carried out in the presence of a compound of the formula RMgCl , wherein R is a C_{1-4} alkyl group.

6.3 A process according to Embodiment 6.2 wherein R is iso-propyl (and RMgCl is iPrMgCl).

- 6.4 A process according to any one of Embodiments 6.1 to 6.3 wherein the reaction is carried out in the presence of a Lewis acid.
- 6.5 A process according to Embodiment 6.4 wherein the Lewis acid is a lanthanide chloride (e.g. LaCl_3 or CeCl_3).
- 5 6.6 A process according to Embodiment 6.4 or 6.5 wherein the Lewis acid is LaCl_3 .
- 6.7 A process according to any one of Embodiments 6.1 to 6.6 wherein the reaction is carried out in a polar, aprotic solvent.
- 6.8 A process according to Embodiment 6.7 wherein the solvent is tetrahydrofuran (THF).
- 10 The above processes can be used in the preparation of 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile or pharmaceutically acceptable salts thereof. Accordingly, in a further aspect, there is provided a process for the preparation of 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile, which process
- 15 comprises:
- i)
- a) a process according to any one of Embodiments 6.1 to 6.8; and/or
- b) a process according to any one of Embodiment 5.1 to 5.5; and/or
- c) a process according to any one of Embodiment 4.1 to 4.8; and/or
- 20 d) a process according to any one of Embodiment 3.1 to 3.6; and/or
- e) a process according to any one of Embodiment 2.1 to 2.6; and/or
- f) a process according to any one of Embodiment 1.1 to 1.7; and
- ii) interconverting a product obtained from step i) into 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile, for
- 25 example by reacting a compound of formula (18) with a methylating agent (such as HCHO in the presence of a reducing agent such as $(\text{AcO}_3)\text{BH}$); and
- iii) optionally forming a pharmaceutically acceptable salt of 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile.

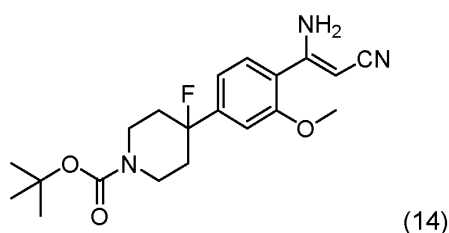
Alternatively, the invention provides a process for the preparation of 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile, which process comprises:

- i)
- 5 a) a process according to claim 4; and/or
 b) a process according to claim 3; and/or
 c) a process according to claim 2; and/or
 d) a process according to claim 1;
- ii) interconverting a product obtained from step i) to a compound of formula (18);
- 10 iii) interconverting a product obtained from step ii) into 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile, for example by reacting a compound of formula (18) with a methylating agent (such as HCHO in the presence of a reducing agent such as (AcO₃)BH); and
- iv) optionally forming a pharmaceutically acceptable salt of 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile.
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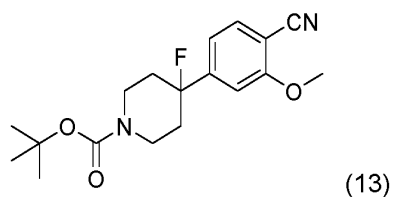
In a further aspect, the invention provides novel intermediates suitable for use in the processes of the invention. It has been found that the intermediates are crystalline and therefore the need for chromatography to purify reaction products is reduced or avoided.

- 20 Accordingly, in further embodiments, the invention provides:

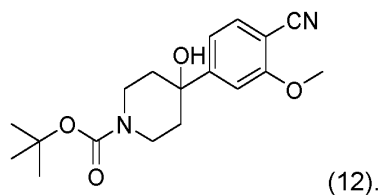
7.1 A compound of the formula (14):



7.2 A compound of the formula (13):



7.3 A compound of the formula (12):



7.4 A compound according to any one of Embodiments 7.1 to 7.3 in a substantially
5 crystalline form.

Further details of crystalline forms of the intermediates used in the improved process are provided below.

Intermediate of Formula (12)

The XRPD diffractogram for a crystalline form of the intermediate of formula (12) is
10 shown in Figure 1.

The X-ray diffraction pattern of the crystalline form of the intermediate of formula (12) exhibits peaks of greatest intensity at the diffraction angles (2θ) set out in Table A-1

<u>Table A-1</u>	
Diffraction Angle (°)	Relative Intensity
10.6 ± 0.2	54
13.3 ± 0.2	100
16.7 ± 0.2	61
17.0 ± 0.2	99
19.9 ± 0.2	52

Accordingly, in further embodiments, the invention provides:

- 7.5 A substantially crystalline form of the compound of formula (12) having an X-ray powder diffraction pattern characterised by the presence of major peaks at the diffraction angles (2θ) 10.6° and/or 13.3° and/or 16.7° and/or 17.0° and/or 19.9° ($\pm 0.2^\circ$).
- 5 7.6 A substantially crystalline form of the compound of formula (12) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 10.6° ($\pm 0.2^\circ$).
- 7.7 A substantially crystalline form of the compound of formula (12) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the
10 diffraction angle (2θ) 13.3° ($\pm 0.2^\circ$).
- 7.8 A substantially crystalline form of the compound of formula (12) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 16.7° ($\pm 0.2^\circ$).
- 7.9 A substantially crystalline form of the compound of formula (12) having an X-
15 ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 17.0° ($\pm 0.2^\circ$).
- 7.10 A substantially crystalline form of the compound of formula (12) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 19.9° ($\pm 0.2^\circ$).
- 20 7.11 A substantially crystalline form of the compound of formula (12) having an X-ray powder diffraction pattern characterised by the presence of major peaks at two or more, e.g. three or more, or four or more, and in particular five diffraction angles (2θ) selected from 10.6° , 13.3° , 16.7° , 17.0° and 19.9° ($\pm 0.2^\circ$).
- 7.12 A substantially crystalline form of the compound of formula (12) which exhibits
25 peaks at the diffraction angles set forth in Table A-1 provided above or Table 1 provided below which have a relative intensity of at least 15%.
- 7.13 A substantially crystalline form of the compound of formula (12) which exhibits peaks at the diffraction angles corresponding to those of the X-ray powder diffraction pattern shown in Figure 1.
- 30 7.14 A substantially crystalline form of the compound of formula (12) having an X-ray powder diffraction pattern substantially as shown in Figure 1.

Intermediate of Formula (13)

The XRPD diffractogram for a crystalline form of the intermediate of formula (13) is shown in Figure 2.

- The X-ray diffraction pattern of the crystalline form of the intermediate of formula (13) exhibits peaks of greatest intensity at the diffraction angles (2θ) set out in Table A-2

Table A-2	
Diffraction Angle ($^{\circ}$)	Relative Intensity
10.8 ± 0.2	87
13.5 ± 0.2	71
14.0 ± 0.2	89
15.7 ± 0.2	91
21.7 ± 0.2	100

Accordingly, in further embodiments, the invention provides:

- 7.15 A substantially crystalline form of the compound of formula (13) having an X-ray powder diffraction pattern characterised by the presence of major peaks at the diffraction angles (2θ) 10.8° and/or 13.5° and/or 14.0° and/or 15.7° and/or 21.7° ($\pm 0.2^{\circ}$).
- 7.16 A substantially crystalline form of the compound of formula (13) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 10.8° ($\pm 0.2^{\circ}$).
- 7.17 A substantially crystalline form of the compound of formula (13) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 13.5° ($\pm 0.2^{\circ}$).
- 7.18 A substantially crystalline form of the compound of formula (13) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 14.0° ($\pm 0.2^{\circ}$).

- 7.19 A substantially crystalline form of the compound of formula (13) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) $15.7^\circ (\pm 0.2^\circ)$.
- 5 7.20 A substantially crystalline form of the compound of formula (13) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) $21.7^\circ (\pm 0.2^\circ)$.
- 10 7.21 A substantially crystalline form of the compound of formula (13) having an X-ray powder diffraction pattern characterised by the presence of major peaks at two or more, e.g. three or more, or four or more, and in particular five diffraction angles (2θ) selected from 10.8° , 13.5° , 14.0° , 15.7° and $21.7^\circ (\pm 0.2^\circ)$.
- 7.22 A substantially crystalline form of the compound of formula (13) which exhibits peaks at the diffraction angles set forth in Table A-2 provided above or Table 2 provided below which have a relative intensity of at least 15%.
- 15 7.23 A substantially crystalline form of the compound of formula (13) which exhibits peaks at the diffraction angles corresponding to those of the X-ray powder diffraction pattern shown in Figure 2.
- 7.24 A substantially crystalline form of the compound of formula (13) having an X-ray powder diffraction pattern substantially as shown in Figure 2.

Intermediate of Formula (14)

- 20 The XRPD diffractogram for a crystalline form of the intermediate of formula (14) is shown in Figure 3.

The X-ray diffraction pattern of the crystalline form of the intermediate of formula (14) exhibits peaks of greatest intensity at the diffraction angles (2θ) set out in Table A-3

Table A-3	
Diffraction Angle ($^\circ$)	Relative Intensity
7.8 ± 0.2	50
14.6 ± 0.2	19
15.4 ± 0.2	26
15.7 ± 0.2	24

18.9 ± 0.2	100
------------	-----

Accordingly, in further embodiments, the invention provides:

7.25 A substantially crystalline form of the compound of formula (14) having an X-ray powder diffraction pattern characterised by the presence of major peaks at the
5 diffraction angles (2θ) 7.8° and/or 14.6° and/or 15.4° and/or 15.7° and/or 18.9° (±0.2°).

7.26 A substantially crystalline form of the compound of formula (14) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 7.8° (±0.2°).

7.27 A substantially crystalline form of the compound of formula (14) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the
10 diffraction angle (2θ) 14.6° (±0.2°).

7.28 A substantially crystalline form of the compound of formula (14) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 15.4° (±0.2°).

7.29 A substantially crystalline form of the compound of formula (14) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the
15 diffraction angle (2θ) 15.7° (±0.2°).

7.30 A substantially crystalline form of the compound of formula (14) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the
20 diffraction angle (2θ) 18.9° (±0.2°).

7.31 A substantially crystalline form of the compound of formula (14) having an X-ray powder diffraction pattern characterised by the presence of major peaks at two or more, e.g. three or more, or four or more, and in particular five diffraction angles (2θ) selected from 10.7°, 14.6°, 15.4°, 15.7° and 18.9° (±0.2°).

7.32 A substantially crystalline form of the compound of formula (14) which exhibits
25 peaks at the diffraction angles set forth in Table A-3 provided above or Table 3 provided below which have a relative intensity of at least 15%.

7.33 A substantially crystalline form of the compound of formula (14) which exhibits peaks at the diffraction angles corresponding to those of the X-ray powder diffraction pattern shown in Figure 3.

7.34 A substantially crystalline form of the compound of formula (14) having an X-ray powder diffraction pattern substantially as shown in Figure 3.

Intermediate of Formula (15)

The XRPD diffractogram for a crystalline form of intermediate of formula (15) is shown in Figure 4.

The X-ray diffraction pattern of the crystalline form of intermediate of formula (15) exhibits peaks of greatest intensity at the diffraction angles (2θ) set out in Table A-4

Table A-4	
Diffraction Angle ($^{\circ}$)	Relative Intensity
5.5 ± 0.2	100
14.5 ± 0.2	22
17.0 ± 0.2	80
18.9 ± 0.2	22
19.3 ± 0.2	39

Accordingly, in further embodiments, the invention provides:

7.35 A compound of formula (15) in a substantially crystalline form.

7.36 A substantially crystalline form of the compound of formula (15) having an X-ray powder diffraction pattern characterised by the presence of major peaks at the diffraction angles (2θ) 5.5° and/or 14.5° and/or 17.0° and/or 18.9° and/or 19.3° ($\pm 0.2^{\circ}$).

7.37 A substantially crystalline form of the compound of formula (15) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 5.5° ($\pm 0.2^{\circ}$).

7.38 A substantially crystalline form of the compound of formula (15) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 14.5° ($\pm 0.2^{\circ}$).

- 7.39 A substantially crystalline form of the compound of formula (15) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) $17.0^\circ (\pm 0.2^\circ)$.
- 7.40 A substantially crystalline form of the compound of formula (15) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) $18.9^\circ (\pm 0.2^\circ)$.
- 7.41 A substantially crystalline form of the compound of formula (15) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) $19.3^\circ (\pm 0.2^\circ)$.
- 7.42 A substantially crystalline form of the compound of formula (15) having an X-ray powder diffraction pattern characterised by the presence of major peaks at two or more, e.g. three or more, or four or more, and in particular five diffraction angles (2θ) selected from 5.5° , 14.5° , 17.0° , 18.9° and $19.3^\circ (\pm 0.2^\circ)$.
- 7.43 A substantially crystalline form of the compound of formula (15) which exhibits peaks at the diffraction angles set forth in Table A-4 provided above or Table 4 provided below which have a relative intensity of at least 15%.
- 7.44 A substantially crystalline form of the compound of formula (15) which exhibits peaks at the diffraction angles corresponding to those of the X-ray powder diffraction pattern shown in Figure 4.
- 7.45 A substantially crystalline form of the compound of formula (15) having an X-ray powder diffraction pattern substantially as shown in Figure 4.

Intermediate of Formula (17)

The XRPD diffractogram for a crystalline form of the intermediate of formula (17) is shown in Figure 5.

- The X-ray diffraction pattern of the crystalline form of the intermediate of formula (17) exhibits peaks of greatest intensity at the diffraction angles (2θ) set out in Table A-5

Table A-5	
Diffraction Angle ($^\circ$)	Relative Intensity
8.8 ± 0.2	27

12.5 ± 0.2	30
15.4 ± 0.2	45
16.3 ± 0.2	100
22.0 ± 0.2	26

Accordingly, in further embodiments, the invention provides:

- 7.46 A compound of formula (17) in a substantially crystalline form.
- 7.47 A substantially crystalline form of the compound of formula (17) having an X-ray powder diffraction pattern characterised by the presence of major peaks at the diffraction angles (2θ) 8.8° and/or 12.5° and/or 15.4° and/or 16.3° and/or 22.0° (±0.2°).
- 7.48 A substantially crystalline form of the compound of formula (17) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 8.8° (±0.2°).
- 10 7.49 A substantially crystalline form of the compound of formula (17) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 12.5° (±0.2°).
- 7.50 A substantially crystalline form of the compound of formula (17) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 15.4° (±0.2°).
- 15 7.51 A substantially crystalline form of the compound of formula (17) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 16.3° (±0.2°).
- 7.52 A substantially crystalline form of the compound of formula (17) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 22.0° (±0.2°).
- 20 7.53 A substantially crystalline form of the compound of formula (17) having an X-ray powder diffraction pattern characterised by the presence of major peaks at two or more, e.g. three or more, or four or more, and in particular five diffraction angles (2θ) selected from 8.8°, 12.5°, 15.4°, 16.3° and 22.0° (±0.2°).
- 25

7.54 A substantially crystalline form of the compound of formula (17) which exhibits peaks at the diffraction angles set forth in Table A-5 provided above or Table 5 provided below which have a relative intensity of at least 15%.

7.55 A substantially crystalline form of the compound of formula (17) which exhibits
5 peaks at the diffraction angles corresponding to those of the X-ray powder diffraction pattern shown in Figure 5.

7.56 A substantially crystalline form of the compound of formula (17) having an X-ray powder diffraction pattern substantially as shown in Figure 5.

Intermediate of Formula (18)

10 The XRPD diffractogram for a crystalline form of the benzenesulphonate salt of the intermediate of formula (18) is shown in Figure 6.

The X-ray diffraction pattern of the crystalline form of the benzenesulphonate salt of the intermediate of formula (18) exhibits peaks of greatest intensity at the diffraction angles (2 θ) set out in Table A-6

<u>Table A-6</u>	
Diffraction Angle (°)	Relative Intensity
4.3 $\pm$ 0.2	100
6.5 $\pm$ 0.2	68
8.6 $\pm$ 0.2	48
15.2 $\pm$ 0.2	33
20.5 $\pm$ 0.2	26

15

Accordingly, in further embodiments, the invention provides:

7.57 A benzenesulphonate salt of a compound of formula (18) in a substantially crystalline form.

7.58 A substantially crystalline form of a benzenesulphonate salt of the compound of
20 formula (18) having an X-ray powder diffraction pattern characterised by the presence of major peaks at the diffraction angles (2 θ) 4.3° and/or 6.5° and/or 8.6° and/or 15.2° and/or 20.5° ($\pm$ 0.2°).

- 7.59 A substantially crystalline form of a benzenesulphonate salt of the compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) $4.3^\circ (\pm 0.2^\circ)$.
- 5 7.60 A substantially crystalline form of a benzenesulphonate salt of the compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) $6.5^\circ (\pm 0.2^\circ)$.
- 7.61 A substantially crystalline form of a benzenesulphonate salt of the compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) $8.6^\circ (\pm 0.2^\circ)$.
- 10 7.62 A substantially crystalline form of a benzenesulphonate salt of the compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) $15.2^\circ (\pm 0.2^\circ)$.
- 7.63 A substantially crystalline form of a benzenesulphonate salt of the compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) $20.5^\circ (\pm 0.2^\circ)$.
- 15 7.64 A substantially crystalline form of a benzenesulphonate salt of the compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of major peaks at two or more, e.g. three or more, or four or more, and in particular five diffraction angles (2θ) selected from 4.3° , 6.5° , 8.6° , 15.2° and $20.5^\circ (\pm 0.2^\circ)$.
- 20 7.65 A substantially crystalline form of a benzenesulphonate salt of the compound of formula (18) which exhibits peaks at the diffraction angles set forth in Table A-6 provided above or Table 6 provided below which have a relative intensity of at least 15%.
- 7.66 A substantially crystalline form of a benzenesulphonate salt of the compound of formula (18) which exhibits peaks at the diffraction angles corresponding to those of the X-ray powder diffraction pattern shown in Figure 6.
- 25 7.67 A substantially crystalline form of a benzenesulphonate salt of the compound of formula (18) having an X-ray powder diffraction pattern substantially as shown in Figure 6.
- 30 The XRPD diffractogram for a crystalline form of the free base of the intermediate of formula (18) is shown in Figure 7.

The X-ray diffraction pattern of the crystalline form of the intermediate of formula (18) exhibits peaks of greatest intensity at the diffraction angles (2θ) set out in Table A-7

Table A-7	
Diffraction Angle (°)	Relative Intensity
9.5 ± 0.2	85
10.2 ± 0.2	87
14.7 ± 0.2	86
15.6 ± 0.2	100
26.2 ± 0.2	67

Accordingly, in further embodiments, the invention provides:

- 5 7.68 A compound of formula (18) in a substantially crystalline form.
- 7.69 A substantially crystalline form of a compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of major peaks at the diffraction angles (2θ) 9.5° and/or 10.2° and/or 14.7° and/or 15.6° and/or 26.2° ($\pm 0.2^\circ$).
- 7.70 A substantially crystalline form of a compound of formula (18) having an X-ray
10 powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 9.5° ($\pm 0.2^\circ$).
- 7.71 A substantially crystalline form of a compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 10.2° ($\pm 0.2^\circ$).
- 15 7.72 A substantially crystalline form of a compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 14.7° ($\pm 0.2^\circ$).
- 7.73 A substantially crystalline form of a compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the
20 diffraction angle (2θ) 15.6° ($\pm 0.2^\circ$).
- 7.74 A substantially crystalline form of a compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of a major peak at the diffraction angle (2θ) 26.2° ($\pm 0.2^\circ$).

- 7.75 A substantially crystalline form of a compound of formula (18) having an X-ray powder diffraction pattern characterised by the presence of major peaks at two or more, e.g. three or more, or four or more, and in particular five diffraction angles (2θ) selected from 9.5° , 10.2° , 14.7° , 15.6° and 26.2° ($\pm 0.2^\circ$).
- 5 7.76 A substantially crystalline form of a compound of formula (18) which exhibits peaks at the diffraction angles set forth in Table A-7 provided above or Table 7 provided below which have a relative intensity of at least 15%.
- 7.77 A substantially crystalline form of a compound of formula (18) which exhibits peaks at the diffraction angles corresponding to those of the X-ray powder diffraction
10 pattern shown in Figure 7.
- 7.78 A substantially crystalline form of a compound of formula (18) having an X-ray powder diffraction pattern substantially as shown in Figure 7.

Further aspects and embodiments of the invention will be apparent from the Examples provided below.

15 **BRIEF DESCRIPTION OF THE DRAWINGS**

- Figure 1 is a XRPD Pattern of a crystalline form of the intermediate of formula (12).
- Figure 2 is a XRPD Pattern of a crystalline form of the intermediate of formula (13).
- Figure 3 is a XRPD Pattern of a crystalline form of the intermediate of formula (14).
- Figure 4 is a XRPD Pattern of a crystalline form of the intermediate of formula (15).
- 20 Figure 5 is a XRPD Pattern of a crystalline form of the intermediate of formula (17).
- Figure 6 is a XRPD Pattern of a crystalline form of a benzenesulphonate salt of the intermediate of formula (18).
- Figure 7 is a XRPD Pattern of a crystalline form of the free base of the intermediate of formula (18).

25 **EXAMPLES**

The invention will now be illustrated, but not limited, by reference to the specific embodiments described in the following examples.

Abbreviations

In the examples, the following abbreviations are used.

	AcOH	acetic acid
	aq	aqueous
	BSA	benzenesulfonic acid
	DAST	diethylaminosulfur trifluoride
5	DCM	dichloromethane
	DIPEA	N,N-diisopropylethylamine
	DMSO	dimethylsulfoxide
	EtOAc	ethyl acetate
	EtOH	ethanol
10	h	hour(s)
	HPLC	high performance liquid chromatography
	iPrOAc	isopropyl acetate
	iPrMgCl	isopropylmagnesium chloride
	KF	Karl Fisher
15	LC	liquid chromatography
	LCMS	liquid chromatography-mass spectrometry
	MeCN	acetonitrile
	min	minute(s)
	MgSO ₄	magnesium sulfate
20	NMR	nuclear magnetic resonance
	RT	retention time
	THF	tetrahydrofuran

Analytical Methods

25

HPLC Method 1

HPLC analysis was carried out on an Agilent 1100 series HPLC system. The column used was an Aquity BEH Phenyl; 30 x 4.6mm, 1.7 µm particle size (Ex Waters, PN: 186004644). The flow rate was 2.0 mL/min. Mobile phase A was Water :

30 Trifluoroacetic acid (100:0.03%) and mobile phase B was Acetonitrile : Trifluoroacetic acid (100:0.03%). Detection was by UV at 210 nm. The injection volume was 5 µL, column temperature 40 °C and the following gradient was used:

Time	%A	%B
0	95	5
5.2	5	95
5.7	5	95
5.8	95	5
6.2	95	5

HPLC Method 2

- HPLC analysis was carried out on an Agilent 1110 series HPLC system. The column used was an Aquity BEH Phenyl; 30 x 4.6mm, 1.7 μ m particle size (Ex Waters, PN: 186004644). The flow rate was 2.0 mL/min. Mobile phase A was Water : Trifluoroacetic acid (100:0.03%) and mobile phase B was Acetonitrile : Trifluoroacetic acid (100:0.03%). Detection was by UV at 210 nm. The injection volume was 5 μ L, column temperature 40 °C and the following gradient was used:

Time (min)	%A	%B
0	95	5
5	95	5
15	5	95
16	5	95
16.5	95	5
17	95	5

10 HPLC Method 3

- HPLC analysis was carried out on an Agilent 1100/1200 series liquid chromatograph. The column used was an XSelect Phenyl-Hexyl; 150 x 4.6mm, 2.5 μ m particle size (Ex Waters, PN: 186006735). The flow rate was 1.0 mL/min. Mobile phase A was 10mM Ammonium Acetate (pH 5.8) and mobile phase B was Acetonitrile 100%. Detection was by UV at 302 nm. The injection volume was 5 μ L and column temperature 50 °C and the following gradient was used:

Time (min)	%A	%B
0	95	5
20	5	95
24.5	5	95
25	95	5

Proton-NMR

- Structures of all intermediates were confirmed from their ^1H NMR spectra which were collected using a JEOL ECX 400MHz spectrometer equipped with an auto-sampler. The samples were dissolved in a suitable deuterated solvent for analysis. The data was acquired using Delta NMR Processing and Control Software version 4.3.

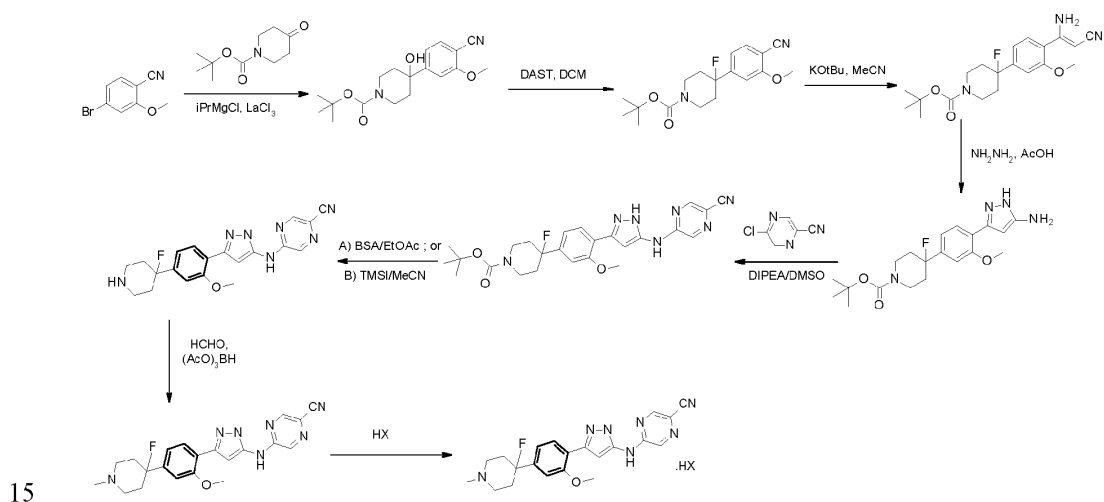
X-Ray Powder Diffraction (XRPD)

- 25 X-Ray Powder Diffraction patterns were collected on a PANalytical diffractometer using Cu K α radiation (45kV, 40mA), θ - θ goniometer, focusing mirror, divergence slit

(1/2"), soller slits at both incident and divergent beam (4mm) and a PIXcel detector. The software used for data collection was X'Pert Data Collector, version 2.2f and the data was presented using X'Pert Data Viewer, version 1.2d. XRPD patterns were acquired under ambient conditions via a transmission foil sample stage (polyimide - Kapton, 12.7µm thickness film) under ambient conditions using a PANalytical X'Pert PRO. The data collection range was 2.994 - 35°2θ with a continuous scan speed of 0.202004°s⁻¹.

10 Example 1

5-[[5-[4-(4-Fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile was prepared as outlined in the reaction scheme shown below.



Step 1: tert-Butyl 4-(4-cyano-3-methoxy-phenyl)-4-hydroxy-piperidine-1-carboxylate

To a 2 L vessel under nitrogen was charged 4-bromo-2-methoxybenzonitrile (125 g, 589 mmol) and anhydrous THF (375 mL). The slurry was cooled to 0°C. A 2M solution of iPrMgCl in THF (530 mL, 1.06 mol) was charged at 0-10°C over 20 min. The batch was stirred out at 0-5°C for 2 h. A 0.6M solution of LaCl₃·2LiCl in THF (196 mL, 118 mmol) was charged over 15 min at 0-5°C. After 30 min, a solution of N-Boc-4-piperidone (146.7 g, 736 mmol) in anhydrous THF (375 mL) was charged over 25 min at 0-15°C. After 30 min stirring, 10% AcOH (750 mL, 1.31 mol) was charged over 15 min at 0-30°C. The organic layer was separated off and concentrated to remove residual THF. The aqueous layer was extracted with TBME (750 mL) and combined

with the concentrated organic layer. Water (250 mL) was charged, the batch stirred and the organic layer separated off and dried (MgSO_4). The batch was concentrated *in vacuo*. The crude material was dissolved in diisopropylether (500 mL) and transferred to a clean 2L vessel along with additional diisopropylether (125 mL). The batch was

5 heated to 60°C and heptanes (500 mL) charged over 15 min at 55-60°C. The batch was cooled to 10°C over 5 h and then stirred overnight to give a slurry. Heptanes (375 mL) were charged, and the batch cooled to 0 °C for 30 min. The solids were filtered off and washed with an ice-cold mixture of diisopropylether (125 mL) and heptanes (125 mL). The material was dried at 40°C to afford the title compound as a white solid (126

10 g, 64% yield).

HPLC (Method 1) RT 2.97 min, 99.0%. ^1H NMR purity >95%.

^1H NMR (CDCl_3) δ 7.49 (d, J = 8.0 Hz, 1H), 7.16 (s, 1H), 7.04 (d, J = 6.4 Hz, 1H), 4.05 (br s, 2H), 3.93 (s, 3H), 3.89 (brs, 2H), 2.04 (s, 1H), 1.94 (brs, 2H), 1.67 (d, J = 12.8

15 Hz, 2H), 1.457 (s, 9H).

The XRPD Diffraction Pattern of the product is shown in Figure 1 and a list of XRPD peaks is shown in Table 1 below.

20 Table 1

Pos. [°2Th.]	Height [cts]	FWHM [°2Th.]	d-spacing [Å]	Rel. Int. [%]
5.6000	1735.69	0.0768	15.78189	21.76
8.4803	292.33	0.0768	10.42688	3.66
8.8402	201.55	0.0768	10.00328	2.53
10.5646	4320.08	0.0768	8.37400	54.16
11.3121	936.29	0.1023	7.82226	11.74
11.6533	594.49	0.0768	7.59402	7.45
12.3565	122.26	0.1023	7.16341	1.53
13.0852	3130.62	0.0768	6.76603	39.25
13.2823	7977.08	0.1023	6.66609	100.00
14.0532	2954.03	0.1023	6.30211	37.03
14.5131	2409.62	0.1279	6.10342	30.21
15.2683	1843.56	0.1279	5.80317	23.11
15.6991	525.46	0.1023	5.64489	6.59
16.6487	4864.57	0.1279	5.32502	60.98
17.0043	7918.32	0.1279	5.21443	99.26
17.4105	1874.34	0.1279	5.09370	23.50
17.7688	744.06	0.1279	4.99179	9.33
18.4513	203.57	0.1279	4.80864	2.55
18.9950	271.50	0.1023	4.67223	3.40
19.9165	4151.30	0.1279	4.45808	52.04
20.5065	1486.53	0.1023	4.33113	18.64
21.1127	3158.29	0.1279	4.20812	39.59
21.3170	1437.40	0.0768	4.16824	18.02
21.7063	653.99	0.1023	4.09436	8.20
22.0421	1189.78	0.1279	4.03274	14.92

22.4436	940.52	0.1535	3.96150	11.79
22.8199	488.42	0.1023	3.89701	6.12
23.1044	159.67	0.1535	3.84967	2.00
23.5132	264.26	0.1279	3.78366	3.31
24.4148	1857.74	0.1535	3.64593	23.29
24.6907	2508.89	0.1535	3.60581	31.45
25.0496	309.28	0.1791	3.55497	3.88
25.7063	1933.03	0.2303	3.46562	24.23
26.1593	391.11	0.1535	3.40662	4.90
26.4576	86.37	0.1023	3.36889	1.08
26.8516	160.52	0.1791	3.32034	2.01
27.2606	435.57	0.1791	3.27145	5.46
27.7590	318.75	0.1279	3.21383	4.00
28.4296	471.16	0.1535	3.13953	5.91
28.6924	469.86	0.1791	3.11138	5.89
29.3541	477.03	0.2814	3.04273	5.98
30.3127	416.40	0.1791	2.94865	5.22
30.9007	88.21	0.1535	2.89387	1.11
31.5317	736.32	0.2047	2.83738	9.23
32.1524	173.14	0.1023	2.78402	2.17
32.8573	113.25	0.1791	2.72588	1.42
33.3269	36.43	0.1535	2.68854	0.46
33.8229	506.29	0.2047	2.65024	6.35
34.5475	84.42	0.1535	2.59629	1.06

Step 2: tert-Butyl 4-(4-cyano-3-methoxy-phenyl)-4-fluoro-piperidine-1-carboxylate

- To a 2 L flask under nitrogen was charged DCM (1.2 L) and DAST (69.8 g, 133 mmol). The solution was cooled to -10°C. A solution of tert-butyl 4-(4-cyano-3-methoxy-phenyl)-4-hydroxy-piperidine-1-carboxylate (120 g, 361 mmol) in DCM (0.24 L) was charged over 1 h at -10°C. After the addition was complete the reaction was warmed to 15-20°C for 1 h. To a 2nd vessel was charged potassium bicarbonate (240 g, 2.40 mol) and water (1 L). The batch was stirred at room temperature to give a solution. The reaction solution was transferred into the aq. potassium bicarbonate solution over 20 min (nitrogen transfer) at 15-25°C. DCM (50 mL) was used as a line rinse. The quenched batch was stirred for 15 min, and the pH checked (>7). The organic layer was separated off. The aqueous layer was extracted with DCM (240 mL), with water (150 mL) added to aid the separation. The organic layers were combined, dried (MgSO₄) and concentrated in vacuo. Diisopropylether (360 mL) was added to dissolve the crude material and concentrated in vacuo to give a white solid (114 g). To a portion of the crude material (100 g) was charged diisopropylether (400 mL) and heptanes (400 mL). The batch was heated to 70 °C to afford a solution, which was cooled to ambient temperature over 1 h and stirred overnight. The batch was filtered, and the solids washed with a mixture of diisopropylether (100 mL) and heptanes (100 mL) to afford 80 g. The material was purified further, diisopropylether (240 mL) and heptanes (240 mL) were added. The batch was heated to 70°C to afford a solution

which was cooled to ambient temperature over 1 h. The batch was filtered, and the solids washed with a mixture of diisopropylether (80 mL) and heptanes (80 mL) to afford the title compound as a white solid (72.6 g, 69% yield). HPLC (method 2) RT 10.58 min, 99.2%. ¹H NMR purity >95%.

5

¹H NMR (CDCl₃) δ 7.54 (d, *J* = 8.8 Hz, 1H), 7.01 (s, 1H), 6.91 (d, *J* = 8.0 Hz, 1H), 4.13 (br s, 2H), 3.95 (s, 3H), 3.14 (brs, 2H), 2.00-1.91 (m, 4H), 1.28 (s, 9H).

10 The XRPD Diffraction Pattern of the product is shown in Figure 2 and a list of XRPD peaks is shown in Table 2 below.

Table 2

Pos. [°2Th.]	Height [cts]	FWHM [°2Th.]	d-spacing [Å]	Rel. Int. [%]
5.5759	250.24	0.3070	15.85005	4.90
7.5637	321.23	0.1023	11.68836	6.29
7.7929	345.44	0.1023	11.34503	6.76
8.5029	2545.21	0.1023	10.39922	49.80
8.8671	2621.51	0.1023	9.97295	51.30
9.8931	290.90	0.1023	8.94087	5.69
10.2574	791.90	0.0768	8.62410	15.50
10.7802	4447.72	0.1023	8.20702	87.03
11.2298	256.52	0.1023	7.87941	5.02
11.9615	1025.58	0.1023	7.39905	20.07
12.4050	1531.64	0.1023	7.13550	29.97
12.9069	2973.82	0.0768	6.85914	58.19
13.0954	1177.13	0.0512	6.76078	23.03
13.5236	3618.70	0.1023	6.54770	70.81
13.9781	4563.06	0.1023	6.33579	89.29
14.2608	2190.09	0.1023	6.21081	42.85
14.6423	474.92	0.0768	6.04984	9.29
14.8791	553.09	0.0768	5.95410	10.82
15.3807	1482.72	0.1023	5.76104	29.01
15.7382	4638.02	0.1279	5.63096	90.75
16.3321	1449.96	0.1791	5.42752	28.37
16.7161	2547.86	0.1023	5.30370	49.85
16.9480	990.51	0.0512	5.23164	19.38
17.2303	1839.29	0.1279	5.14654	35.99
17.7874	2089.46	0.1023	4.98661	40.88
18.1798	668.68	0.1279	4.87985	13.08
18.6918	2219.86	0.1279	4.74732	43.44
18.8618	1893.05	0.1279	4.70490	37.04
19.2793	497.37	0.0768	4.60395	9.73
19.4832	937.67	0.1279	4.55623	18.35
19.9611	751.31	0.1023	4.44820	14.70
20.2790	900.98	0.1535	4.37920	17.63
20.7647	1357.93	0.1279	4.27785	26.57
21.0645	1929.94	0.0768	4.21764	37.76
21.7471	5110.63	0.1279	4.08677	100.00
22.1444	252.94	0.1535	4.01434	4.95
22.6313	1101.76	0.1535	3.92906	21.56

23.1518	1724.31	0.2047	3.84189	33.74
23.8098	608.11	0.1535	3.73720	11.90
24.3171	813.83	0.1535	3.66036	15.92
24.5245	646.68	0.1023	3.62987	12.65
25.1723	668.59	0.1535	3.53791	13.08
25.5338	301.43	0.1279	3.48863	5.90
25.8660	765.04	0.1279	3.44459	14.97
26.4572	570.66	0.1023	3.36894	11.17
26.7806	622.82	0.1279	3.32898	12.19
27.3338	304.36	0.1279	3.26286	5.96
27.6556	424.70	0.1791	3.22562	8.31
28.0073	120.65	0.1279	3.18590	2.36
28.6144	358.98	0.1791	3.11968	7.02
29.0738	202.73	0.1535	3.07142	3.97
29.4243	290.93	0.1023	3.03563	5.69
30.0826	345.67	0.1535	2.97068	6.76
30.9128	96.16	0.2047	2.89277	1.88
31.8509	152.62	0.1535	2.80968	2.99
32.7872	63.21	0.2047	2.73155	1.24
33.2960	75.62	0.2047	2.69097	1.48
34.2242	231.14	0.2047	2.62007	4.52

Step 3: tert-butyl 4-[4-[(Z)-1-amino-2-cyano-vinyl]-3-methoxy-phenyl]-4-fluoro-piperidine-1-carboxylate

- 5 To a 2L vessel was charged tert-butyl 4-(4-cyano-3-methoxy-phenyl)-4-fluoro-piperidine-1-carboxylate (60.2 g, 180 mmol) and anhydrous THF (180.6 mL). The batch was stirred at 15-25°C to achieve a solution. Anhydrous MeCN (18.7 mL, 360 mmol) was charged. A 1M solution of potassium tert-butoxide in THF (540 mL, 540 mmol) was charged over 10 min at 15-25°C followed by a line rinse (THF 60 mL). The
- 10 batch was then warmed to 40°C for 4 h. The batch was cooled to 15-25°C and water (16.3 mL, 900 mmol) charged. After 10 min, the batch was concentrated to ~1/4 volume on the rotavapor. The crude material was slurried in water (903 mL) for 30 min at 15-25°C and then filtered. The solids were washed with water (300 mL) and dried at 40°C to afford the title compound as a tan solid (65.0 g, 96% yield). HPLC (method 2):
- 15 RT 10.46 min, 94.4% (plus 1.4% β -ketonitrile). ¹H NMR purity >95%.

¹H NMR (CDCl₃) δ 7.39 (d, *J* = 8.0 Hz, 1H), 7.02 (s, 1H), 6.91 (d, *J* = 7.2 Hz, 1H), 5.31 (brs, 2H), 4.19 (s, 1H), 4.15 (brs, 2H), 3.92 (s, 3H), 3.17 (brs, 2H), 1.98-1.92 (m, 4H), 1.50 (s, 9H)

20

The XRPD Diffraction Pattern of the product is shown in Figure 3 and a list of XRPD peaks is shown in Table 3 below.

Table 3

Pos. [°2Th.]	Height [cts]	FWHM [°2Th.]	d-spacing [Å]	Rel. Int. [%]
5.4689	240.23	0.3582	16.15972	1.94
6.9829	350.51	0.1023	12.65909	2.83
7.8336	6225.23	0.0768	11.28620	50.34
8.3646	316.68	0.1535	10.57091	2.56
10.6621	112.95	0.3070	8.29763	0.91
12.3627	78.59	0.2047	7.15979	0.64
13.4836	60.04	0.1791	6.56700	0.49
13.8994	643.56	0.0768	6.37149	5.20
14.0839	397.10	0.0512	6.28842	3.21
14.6277	2289.66	0.1023	6.05586	18.52
15.0181	1309.61	0.1023	5.89932	10.59
15.4453	3272.62	0.1023	5.73708	26.47
15.7226	3017.13	0.1535	5.63651	24.40
16.5070	378.31	0.1023	5.37040	3.06
16.8754	1343.83	0.1535	5.25397	10.87
17.3024	1331.68	0.1279	5.12528	10.77
18.1709	526.77	0.1023	4.88221	4.26
18.5597	1711.79	0.0512	4.78081	13.84
18.8857	12365.81	0.1279	4.69902	100.00
19.4039	218.88	0.0768	4.57467	1.77
19.9053	47.78	0.1279	4.46055	0.39
20.7157	785.19	0.1023	4.28786	6.35
21.3288	1704.68	0.1279	4.16597	13.79
21.8478	1251.73	0.1279	4.06816	10.12
22.2264	1458.26	0.1535	3.99972	11.79
22.9060	453.68	0.1535	3.88256	3.67
23.8508	728.77	0.1279	3.73086	5.89
24.9169	1056.31	0.1023	3.57360	8.54
25.1239	1076.77	0.1279	3.54462	8.71
25.9638	51.11	0.1535	3.43183	0.41
26.8630	528.50	0.1535	3.31896	4.27
27.3926	395.22	0.1279	3.25599	3.20
28.1993	309.51	0.1279	3.16465	2.50
28.5628	638.11	0.1279	3.12519	5.16
29.0396	145.63	0.1535	3.07496	1.18
29.8128	764.20	0.2047	2.99695	6.18
30.0601	346.53	0.1023	2.97285	2.80
30.3923	252.10	0.1535	2.94111	2.04
30.7651	93.59	0.1535	2.90632	0.76
31.3153	74.69	0.1535	2.85650	0.60
31.6360	282.60	0.1535	2.82827	2.29
32.0261	405.16	0.1279	2.79471	3.28
32.8034	143.11	0.1279	2.73024	1.16
34.4285	200.93	0.2047	2.60500	1.62

Step 4: tert-butyl 4-[4-(5-amino-1H-pyrazol-3-yl)-3-methoxy-phenyl]-4-fluoro-piperidine-1-carboxylate

5

To tert-butyl 4-[4-[(Z)-1-amino-2-cyano-vinyl]-3-methoxy-phenyl]-4-fluoro-piperidine-1-carboxylate (61.4 g, 163.6 mmol) was charged EtOH (246 mL) and the batch stirred at 15-25°C. Hydrazine monohydrate (9.6 mL, 196 mmol) was charged followed by glacial

acetic acid (11.2 mL, 196 mmol). The batch was warmed to 75°C for 2 h. The batch was cooled to 15-25°C, and water (614 mL) charged. After 30 min stirring, the solids were filtered off and washed with water (2x246 mL). The material was dried at 50°C to afford the title compound an off-white solid (58.6 g, 91.7% yield). HPLC (method 1):

5 97.7% (1.6% amide). KF water measurement: 1.3%.

To reduce levels of the amide side product a portion of the material (49.4g) was slurried at 50°C with diisopropyl ether (250 mL) for 30 min and then isolated at 15-25°C. The solids were washed with diisopropyl ether (50 mL) and oven dried to afford 47.7g stage 4. HPLC (method): 0.8% amide. A portion of the material (41.5g) was
 10 dissolved in DCM (415 mL) at 15-25°C and washed with 1M K₂CO₃ (2x100 mL). The organic layer was dried (MgSO₄), concentrated and oven dried at 50°C to afford the title compound (39.7 g, 58% yield) as a pale-yellow solid. HPLC (method 3): RT 12.94 min, 96.4%. ¹H NMR purity >95%.

15 ¹H NMR (CDCl₃) δ 10.35 (s, 1H), 7.54 (d, *J* = 7.6 Hz, 1H), 7.04 (s, 1H), 6.93 (d, *J* = 8.0 Hz, 1H), 5.99 (s, 1H), 4.16 (brs, 2H), 3.98 (s, 3H), 3.16 (brs, 2H), 3.16 (brs, 2H), 2.06-1.94 (m, 4H), 1.48 (s, 9H).

The XRPD Diffraction Pattern of the product is shown in Figure 4 and a list of XRPD
 20 peaks is shown in Table 4 below.

Table 4

Pos. [°2Th.]	Height [cts]	FWHM [°2Th.]	d-spacing [Å]	Rel. Int. [%]
5.4701	7934.94	0.1023	16.15636	100.00
9.0334	1038.47	0.1535	9.78967	13.09
11.0578	329.27	0.1023	8.00157	4.15
11.7201	725.22	0.1279	7.55088	9.14
12.4477	195.58	0.2047	7.11111	2.46
13.8066	261.35	0.1023	6.41411	3.29
14.4749	1757.29	0.1791	6.11945	22.15
15.4324	355.29	0.1791	5.74185	4.48
15.9245	437.99	0.1535	5.56549	5.52
16.3898	862.30	0.2558	5.40854	10.87
17.0079	6332.70	0.1791	5.21334	79.81
17.6039	1629.07	0.1535	5.03817	20.53
18.2161	517.84	0.1535	4.87020	6.53
18.9472	1746.24	0.1791	4.68389	22.01
19.3431	3115.50	0.2303	4.58891	39.26
20.9486	457.60	0.1791	4.24072	5.77
21.9689	245.25	0.1023	4.04602	3.09
22.6739	946.42	0.3070	3.92178	11.93
23.5183	1201.83	0.1535	3.78285	15.15
24.1304	458.22	0.2558	3.68826	5.77
25.7751	195.93	0.2558	3.45652	2.47
27.2189	933.74	0.2047	3.27637	11.77

28.7572	263.63	0.4093	3.10451	3.32
30.3511	41.55	0.6140	2.94501	0.52
31.4234	54.23	0.3070	2.84692	0.68
33.4134	66.59	0.4093	2.68178	0.84

Step 5: tert-butyl 4-[4-[5-[(5-cyanopyrazin-2-yl)amino]-1H-pyrazol-3-yl]-3-methoxy-phenyl]-4-fluoro-piperidine-1-carboxylate

- 5 To a 500 mL vessel under nitrogen was charged tert-butyl 4-[4-(5-amino-1H-pyrazol-3-yl)-3-methoxy-phenyl]-4-fluoro-piperidine-1-carboxylate (32.4 g, 83 mmol) followed by 5-chloro-2-cyanopyrazine (12.34 g, 91.3 mmol) and anhydrous DMSO (64.8 mL). DIPEA (18.1 ml, 103.8 mmol) was charged, and the batch warmed to 50°C for 20 h. The batch was cooled to ambient temperature and iPrOAc (162 mL) charged. The
- 10 resulting solution was poured into water (324 mL) at 15-30°C, and the batch stirred for 1 h. The batch was filtered and washed with water (324 mL) and iPrOAc (162 mL). The solids were oven dried at 50°C to afford the title compound as a tan solid (39.6g, 94% yield). HPLC (method 3): RT 15.57 min, 97.6%. ¹H NMR purity >95%.
- 15 ¹H NMR (DMSO-d₆) δ 12.65 (s, 1H), 10.76 (s, 1H), 8.66 (s, 1H), 8.51 (brs, 1H), 7.67 (d, *J* = 8.0 Hz, 1H), 7.14 (s, 1H), 7.09 (d, *J* = 7.2 Hz, 1H), 4.01 (brs, 2H), 3.93 (s, 3H), 3.05 (brs, 2H), 2.13-1.88 (m, 4H), 1.42 (s, 9H).

- The XRPD Diffraction Pattern of the product is shown in Figure 5 and a list of XRPD
- 20 peaks is shown in Table 5 below.

Table 5

Pos. [°2Th.]	Height [cts]	FWHM [°2Th.]	d-spacing [Å]	Rel. Int. [%]
4.1954	569.49	0.0768	21.06200	7.12
5.3479	308.77	0.2558	16.52527	3.86
8.4656	363.88	0.1279	10.44499	4.55
8.7877	2144.83	0.1023	10.06290	26.83
9.4696	1383.59	0.1023	9.33971	17.31
11.7687	161.36	0.1279	7.51981	2.02
12.5013	2436.64	0.1023	7.08073	30.48
13.6052	1343.68	0.1279	6.50862	16.81
14.0353	243.89	0.1279	6.31012	3.05
14.9385	642.13	0.1279	5.93054	8.03
15.4436	3595.84	0.1279	5.73771	44.98
16.3066	7993.52	0.1279	5.43594	100.00
17.1845	911.03	0.1279	5.16015	11.40
17.7188	818.95	0.1023	5.00576	10.25
17.9227	471.10	0.0768	4.94926	5.89
18.1445	351.66	0.0768	4.88926	4.40
18.5853	1311.37	0.1279	4.77428	16.41
19.7149	578.53	0.1279	4.50319	7.24

20.2896	95.06	0.1535	4.37693	1.19
21.3211	567.64	0.1535	4.16744	7.10
22.0264	2078.15	0.1279	4.03558	26.00
22.3775	1697.27	0.1535	3.97304	21.23
23.3408	330.06	0.1279	3.81121	4.13
23.5470	528.13	0.1023	3.77831	6.61
23.7850	396.22	0.1023	3.74103	4.96
24.1442	509.60	0.1279	3.68618	6.38
24.9050	295.74	0.1023	3.57528	3.70
25.6568	660.72	0.1279	3.47219	8.27
25.8774	678.62	0.1535	3.44308	8.49
26.8002	260.78	0.1535	3.32659	3.26
27.5412	451.11	0.1535	3.23876	5.64
28.9481	108.84	0.1535	3.08447	1.36
29.3280	100.05	0.1535	3.04538	1.25
30.3511	235.36	0.1279	2.94501	2.94
31.3973	62.73	0.5117	2.84923	0.78
32.5428	164.39	0.1279	2.75150	2.06
34.4863	17.53	0.2558	2.60076	0.22

Step 6A: 5-[[3-[4-(4-fluoro-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-5-yl]amino]pyrazine-2-carbonitrile

- 5 To a flask under nitrogen was charged tert-butyl 4-[4-[5-[(5-cyanopyrazin-2-yl)amino]-1H-pyrazol-3-yl]-3-methoxy-phenyl]-4-fluoro-piperidine-1-carboxylate (1 g, 2.03 mmol) and 1,4-dioxane (15 mL). The batch was heated to 80-85°C for 1 h then cooled to ambient and the solvent was removed *in vacuo*. To the crude material was charged EtOAc (30 mL) and the batch heated to 60°C. Benzenesulfonic acid (801 mg, 5.08
- 10 mmol) was charged, and the slurry heated at 60°C for 26 h. The batch was cooled to ambient and filtered. The solids were washed with EtOAc (10 mL) and oven dried at 50°C to afford the title compound as its besylate salt as a light brown solid (1.15 g, 84%). HPLC (method 3): RT 9.09 min, 97.9%. ¹H NMR: 41% BSA, 0.8% EtOAc, 58% title compound.

15

The XRPD Diffraction Pattern of the product is shown in Figure 6 and a list of XRPD peaks is shown in Table 6 below.

Table 6

Pos. [°2Th.]	Height [cts]	FWHM [°2Th.]	d-spacing [Å]	Rel. Int. [%]
4.2512	8202.52	0.1279	20.78537	100.00
5.4758	110.94	0.4093	16.13946	1.35
6.5407	5574.71	0.1279	13.51398	67.96
8.6054	3916.84	0.1279	10.27559	47.75
8.9584	1846.09	0.1279	9.87150	22.51
10.1438	613.00	0.1279	8.72042	7.47
11.2947	167.75	0.1791	7.83431	2.05

12.4583	383.33	0.1279	7.10507	4.67
12.9796	700.07	0.1791	6.82084	8.53
14.5882	1324.20	0.1279	6.07217	16.14
15.2029	2717.18	0.2814	5.82799	33.13
16.2645	656.33	0.1279	5.44991	8.00
16.6296	534.95	0.1535	5.33109	6.52
17.0081	631.25	0.1279	5.21329	7.70
17.4344	246.19	0.1535	5.08675	3.00
18.2303	299.90	0.1791	4.86644	3.66
18.8886	1329.06	0.2558	4.69829	16.20
19.6313	441.99	0.1535	4.52220	5.39
19.8707	686.74	0.1023	4.46825	8.37
20.4588	2148.08	0.2303	4.34112	26.19
21.0567	337.15	0.2047	4.21919	4.11
21.7739	1025.60	0.1791	4.08180	12.50
22.2106	1157.29	0.2047	4.00252	14.11
22.6825	592.56	0.2047	3.92031	7.22
23.4872	498.04	0.2303	3.78779	6.07
24.4366	1367.64	0.2303	3.64273	16.67
25.5187	1290.15	0.2047	3.49066	15.73
26.7626	252.40	0.2047	3.33119	3.08
27.3332	764.66	0.2558	3.26293	9.32
29.1449	145.36	0.2558	3.06409	1.77
29.5113	139.30	0.2558	3.02688	1.70
30.2736	39.41	0.3070	2.95237	0.48
31.2593	222.46	0.2047	2.86148	2.71
33.5239	148.11	0.1791	2.67319	1.81

Step 6B: 5-[[3-[4-(4-fluoro-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-5-yl]amino]pyrazine-2-carbonitrile

- 5 As an alternative to Step 6A above, 5-[[3-[4-(4-fluoro-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-5-yl]amino]pyrazine-2-carbonitrile was also prepared according to the following method.

- To tert-butyl 4-[4-[5-[(5-cyanopyrazin-2-yl)amino]-1H-pyrazol-3-yl]-3-methoxy-phenyl]-4-fluoro-piperidine-1-carboxylate (1.0 g, 2.03 mmol) was added MeCN (10 mL) followed by iodotrimethylsilane (577 μ L, 4.06 mmol) at 0-20°C. After 30 min 10% aqueous potassium carbonate (5 mL, 3.62 mmol) was charged (off-gassing observed) and the batch stirred for 30 min. The solids were then filtered off and washed with a mixture of MeCN (2 mL) and water (2 mL). The solids were oven dried at 50°C to afford the title compound as a light brown solid (766 mg, 96%). HPLC (method 3): RT 9.09 min, 98.8%. ¹H NMR purity >95%.

¹H NMR (DMSO-d₆) δ 12.65 (s, 1H), 10.50 (s, 1H), 8.66 (s, 1H), 8.51 (brs, 1H), 7.67 (d, J = 8.4 Hz, 1H), 7.10 (s, 1H), 7.05 (d, J = 8.0 Hz, 1H), 3.92 (s, 3H), 3.48 (brs, 1H), 2.93-2.83 (m, 4H), 2.08-1.82 (m, 4H).

- 5 The XRPD Diffraction Pattern of the product is shown in Figure 7 and a list of XRPD peaks is shown in Table 7 below.

Pos. [°2Th.]	Height [cts]	FWHM [°2Th.]	d-spacing [Å]	Rel. Int. [%]
5.4686	133.02	0.3070	16.16070	23.89
7.2285	87.91	0.2047	12.22954	15.78
9.5118	475.92	0.1535	9.29834	85.46
10.2059	482.92	0.1279	8.66747	86.71
14.6692	481.13	0.2047	6.03884	86.39
15.6196	556.90	0.1279	5.67344	100.00
16.7239	82.50	0.5117	5.30122	14.81
18.1495	75.78	0.1535	4.88791	13.61
19.0095	84.49	0.4093	4.66868	15.17
20.0050	137.18	0.2303	4.43855	24.63
21.9383	205.92	0.1023	4.05158	36.98
22.6163	255.58	0.1279	3.93164	45.89
23.4429	70.03	0.2558	3.79484	12.58
24.0880	91.80	0.3070	3.69466	16.48
26.2023	373.13	0.6140	3.40113	67.00
26.9223	294.89	0.3070	3.31178	52.95
31.6514	54.38	0.4093	2.82693	9.76
34.1306	47.75	0.4093	2.62705	8.57

Step 7: 5-[[3-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-5-yl]amino]pyrazine-2-carbonitrile

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To 5-[[3-[4-(4-fluoro-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-5-yl]amino]pyrazine-2-carbonitrile (60.79 g active, 155 mmol) was charged EtOH (608 mL). The batch was stirred at RT and 37% formalin (22.5 mL, 278 mmol) charged. Sodium triacetoxyborohydride (58.95 g, 278 mmol) was charged in four portions over 30 min at 15-25°C. After 2 h, an 8.5% ammonium hydroxide solution (608 mL) was charged over 20 min at <25°C. The batch was cooled to 0-5°C and filtered, washing the cake with water (2 x 304 mL). The wet material was returned to vessel with water (608 mL) and slurried at RT for 30 min. The batch was filtered and washed with water (304 mL). The solids were oven dried at 50°C to afford the title compound (51.4 g, 82% active yield (100% minus water and ethanol)).

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HPLC (Method 3) RT 10.20 min, 97.0%. ¹H NMR purity >95%.

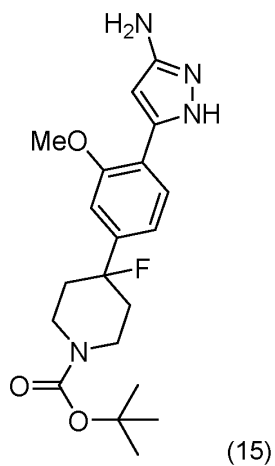
¹H NMR (DMSO-d₆) δ 12.64 (s, 1H), 10.74 (s, 1H), 8.66 (s, 1H), 8.51 (brs, 1H), 7.66 (d, *J* = 8.0 Hz, 1H), 7.12 (s, 1H), 7.07 (d, *J* = 8.8 Hz, 1H), 3.92 (s, 3H), 2.72-2.49 (m, 2H), 2.22-2.09 (m, 4H), 2.12 (s, 3H), 1.93-1.86 (m, 2H).

Equivalents

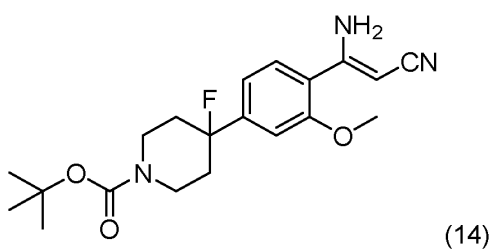
- 5 The foregoing examples are presented for the purpose of illustrating the invention and should not be construed as imposing any limitation on the scope of the invention. It will readily be apparent that numerous modifications and alterations may be made to the specific embodiments of the invention described above and illustrated in the examples without departing from the principles underlying the invention. All such
- 10 modifications and alterations are intended to be embraced by this application.

CLAIMS

1. A process for the preparation of a compound of formula (15):

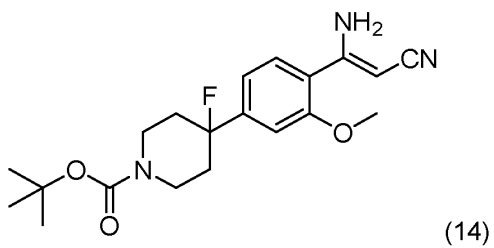


which process comprises reacting a compound of the formula (14):

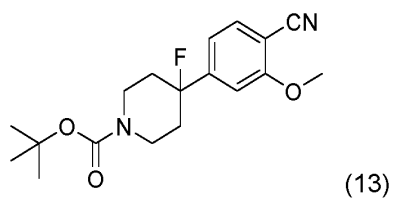


with hydrazine (NH_2NH_2).

2. A process for the preparation of a compound of the formula (14):

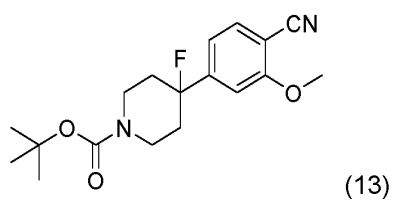


which process comprises reacting a compound of formula (13):

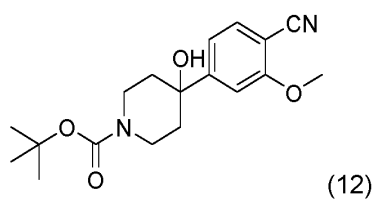


with acetonitrile (CH_3CN) in the presence of a base.

3. A process for the preparation of a compound of the formula (13):

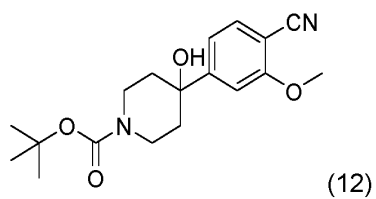


which process comprises reacting a compound of formula (12):

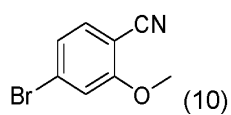


with a deoxyfluorination reagent.

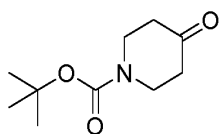
4. A process for the preparation of a compound of the formula (12):



which process comprises reacting a compound of formula (10):

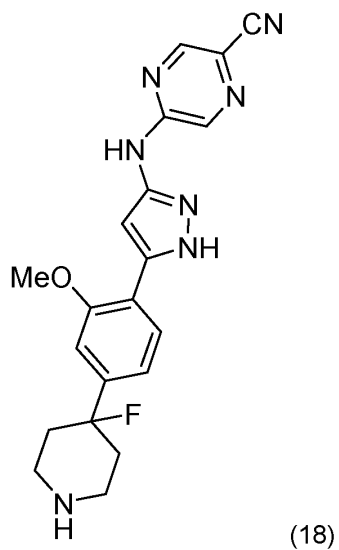


with a compound of formula (11):

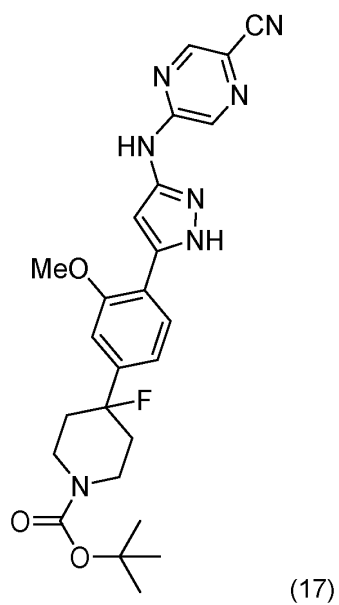


in the presence of a metallating agent, such as a Grignard reagent.

5. A process for the preparation of a compound of the formula (18):

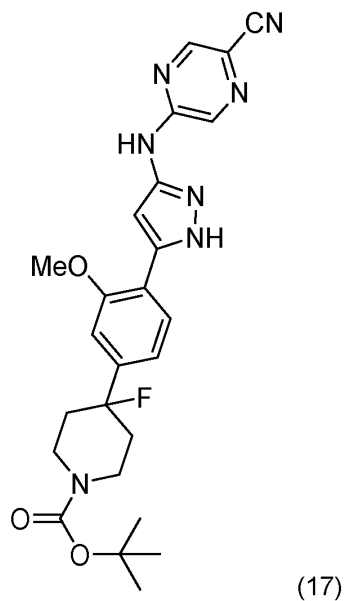


which process comprises reacting a compound of the formula (17):

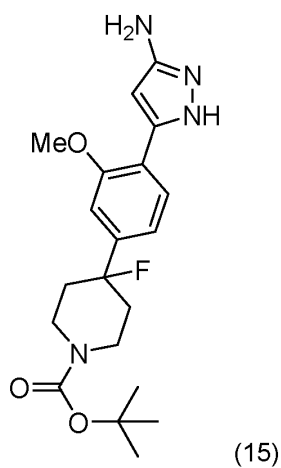


with an alkylsilyl halide or a sulphonic acid.

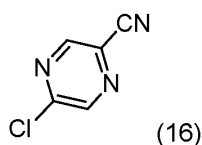
6. A process according to claim 5 which process comprises reacting a compound of the formula (17) with an alkylsilyl halide (such as TMSI).
7. A process according to claim 5 which process comprises reacting a compound of the formula (17) with a sulphonic acid (such as benzene sulphonic acid).
8. A process for the preparation of a compound of the formula (17):



which process comprises the reaction of a compound of the formula (15)



with a compound of the formula (16):



9. A process for the preparation of 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile, which process comprises:

i)

- a) a process according to claim 4; and/or
- b) a process according to claim 3; and/or
- c) a process according to claim 2; and/or
- d) a process according to claim 1; and/or
- e) a process according to claim 8; and/or
- f) a process according to any one of claims 5 to 7; and

ii) interconverting a product obtained from step i) into 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile, for example by reacting a compound of formula (18) with a methylating agent (such as HCHO in the presence of a reducing agent such as $(\text{AcO}_3)\text{BH}$); and

iii) optionally forming a pharmaceutically acceptable salt of 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile.

10. A process for the preparation of 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile, which process comprises:

i)

- a) a process according to claim 4; and/or
- b) a process according to claim 3; and/or
- c) a process according to claim 2; and/or
- d) a process according to claim 1;

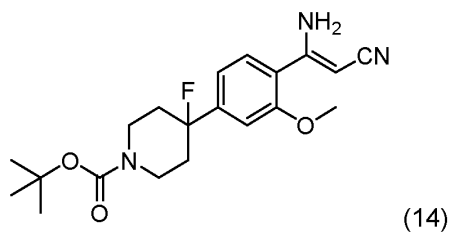
ii) interconverting a product obtained from step i) to a compound of formula (18);

iii) interconverting a product obtained from step ii) into 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile, for

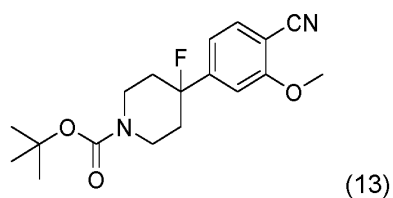
example by reacting a compound of formula (18) with a methylating agent (such as HCHO in the presence of a reducing agent such as $(\text{AcO}_3)\text{BH}$); and

iv) optionally forming a pharmaceutically acceptable salt of 5-[[5-[4-(4-fluoro-1-methyl-4-piperidyl)-2-methoxy-phenyl]-1H-pyrazol-3-yl]amino]pyrazine-2-carbonitrile.

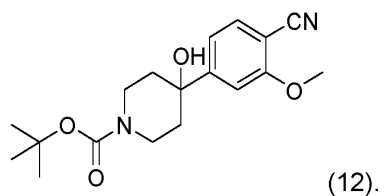
11. A compound of the formula (14):



12. A compound of the formula (13):



13. A compound of the formula (12):



14. A compound according to any one of claims 11 to 13 in a substantially crystalline form.

15. An invention as defined in any one of Embodiments 1.1 to 1.7, 2.1 to 2.6, 3.1 to 3.6, 4.1 to 4.8, 5.1 to 5.5, 6.1 to 6.8 and 7.1 to 7.78 herein.